

Please provide the following information:

This will allow us to suggest the appropriate evaporation source for your application

Customer Name	
Institution	
Address	
E-mail	

1. Which material, element or molecule do you want to evaporate? _____
2. What is the expected operating temperature range? _____
3. What is the typical deposition rate (co-deposition: $\mu\text{m/h}$ or nm/s , doping level etc.)? _____
4. What is the substrate size and material? _____
5. Substrate rotation (yes/no) _____; Deposition homogeneity (+/- %) _____
6. Provide information about the deposition geometry:
 - drawing or sketch of the UHV chamber _____
 - distance from source orifice to substrate _____
 - size of mounting flange, inner diameter of the port _____
 - angular arrangement and position _____
 - type of UHV or MBE system used (Riber 32P, Veeco GEN II, home made ...) _____
7. Environment (e.g. UHV, O_2 background pressure, P, As, Se background pressure ...) _____ mbar
8. Applications (GaAs/AlGaAs MBE, oxid MBE, organic materials, OLED, etc.) _____
9. Source Options / Additional Equipment
 - water cooling shroud needed? _____
 - source shutter needed? _____
 - shutter motorization needed? _____ (electric / pneumatic?: _____)
 - power supply, PID controller? _____
 - increased bakeability (200°C) of cables needed? _____